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| Substitute Form PTO-1449 (Modified) | U.S. Department of Commerce Patent and Trademark Office | Attorney's Docket No. Intel 10559-865001 / P17313 | Application No. 10/649,355 |
| Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b)) IDS filed 09/22/2003 | | Applicant Florence Eschbach et al. | |
| | | Filing Date August 26, 2003 | Group Art Unit 1713 |

| U.S. Patent Documents | | | | | | | |
|-----------------------|-----------|-----------------|------------------|----------|-------|----------|----------------------------|
| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
| | AA | | | | | | |
| | AB | | | | | | |
| | AC | | | | | | |
| | AD | | | | | | |
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| Foreign Patent Documents or Published Foreign Patent Applications | | | | | | | | |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation | |
| | | | | | | | Yes | No |
| | AH | | | | | | | |
| | AI | | | | | | | |
| | AJ | | | | | | | |
| | AK | | | | | | | |
| | AL | | | | | | | |

| Other Documents (include Author, Title, Date, and Place of Publication) | | |
|---|-----------|---|
| Examiner Initial | Desig. ID | Document |
| HLS | AM | D.W. Van Krevelen, with the collaboration of P.J. Hoftyzer; "Properties of Polymers, Their Estimation and Correlation with Chemical Structure," Second, completely revised edition; 1976, Elsevier Scientific Publishing Company, Amsterdam - Oxford - New York |
| | AN | Oshima et al.; Radiation Physics and Chemistry, "Chemical structure and physical properties of radiation-induced crosslinking of polytetrafluoroethylene"; © 2001 Elsevier Science Ltd.; www.elsevier.com/locate/radphyschem |
| | AO | Reu et al.; "Mechanical analysis of hard pellicles for 157 nm lithography," to appear in the Proceedings of the 2001 SPIE Symposium on Optical Microlithography XIV, Vol. 4346, 2001; UW Computational Mechanics Center, University of Wisconsin, Madison, WI 53706; Intel Corporation, Santa Clara, CA 95052 |
| | AP | Kozeki et al.; "Longevity of 193nm/ArF Excimer Pellicle; April 26, 2001; Mitsui Chemicals, Inc., Pellicles Dept. |
| ✓ | AQ | Shu et al.; "Hard Pellicle Study for 157-nm Lithography"; Preprint, to appear in the Proceedings of Photomask Japan, 2002 |

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| Examiner Signature | Date Considered 4-10-06 |
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EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.